

Workflow Automation For High Volume TEM Data Production

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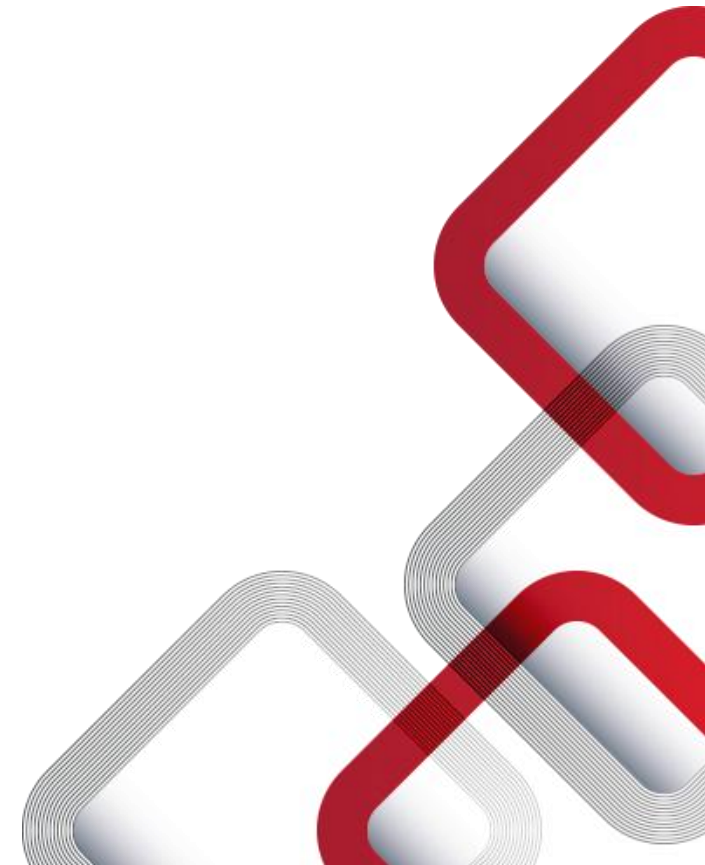
Agenda

1 Industry Trends toward Increasing TEM Usage

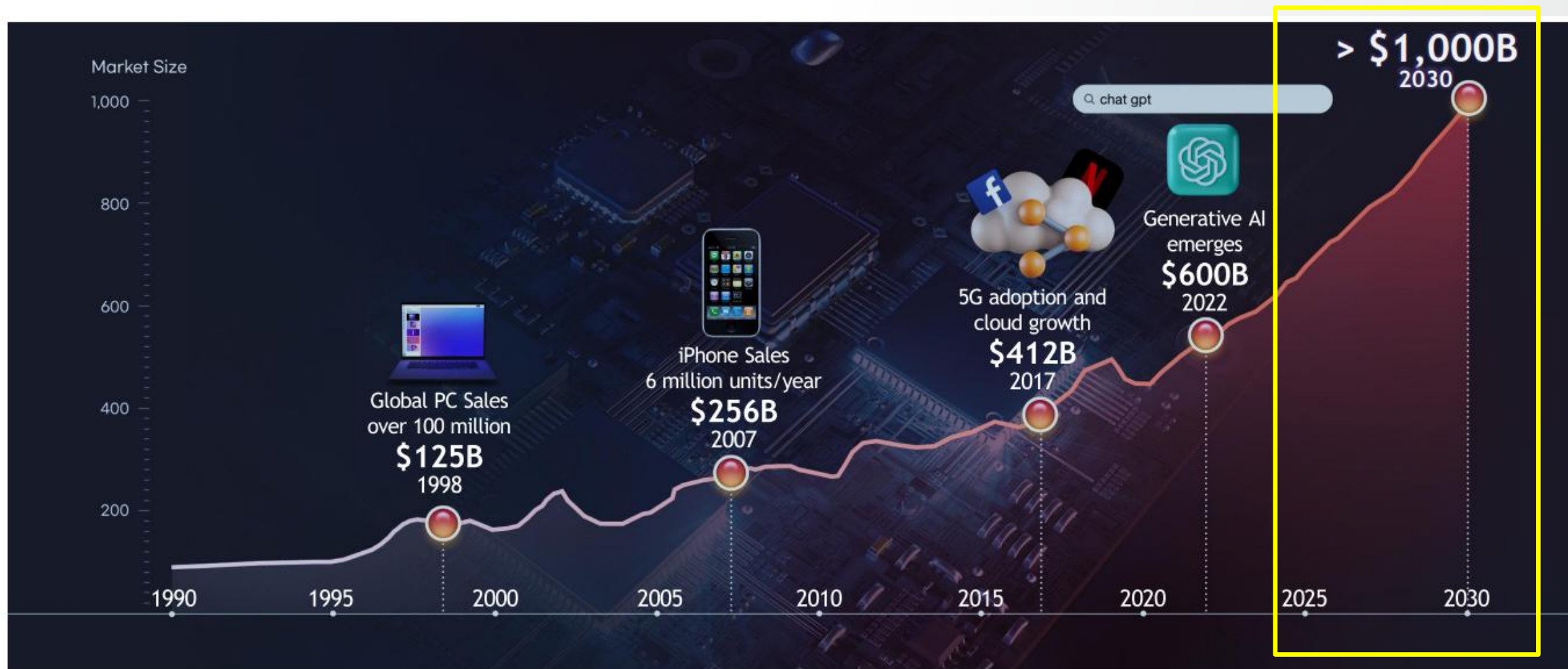
2 Challenges in TEM sample preparation

3 Process Automation in TEM
Preparation and Imaging

4 How Automation is bridging the gap
between Lab and Fab



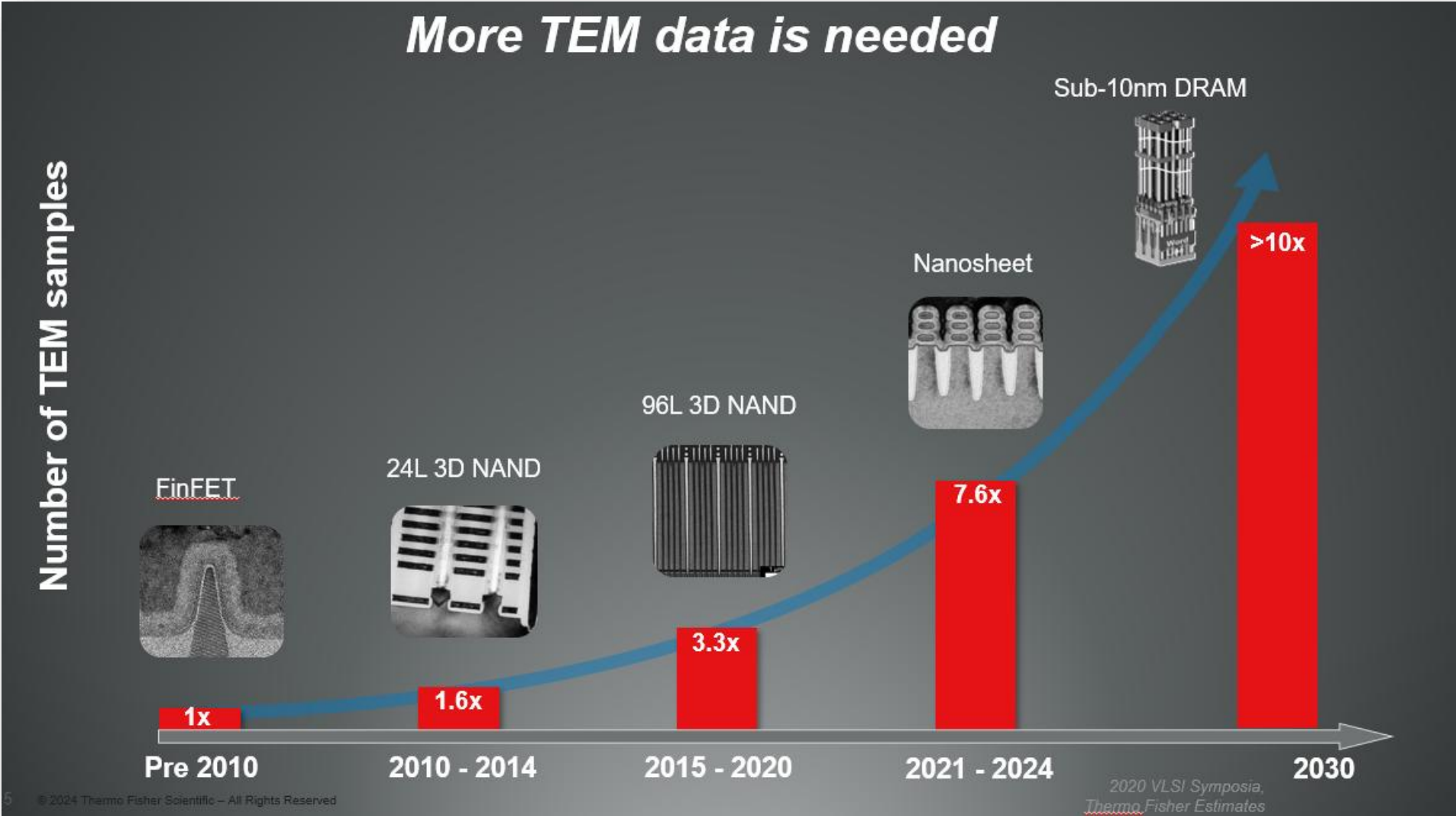
Rapid Growth in Semi is Mainly Driven by AI and HPC



Source: VLSI 2025 SC-1 (SK Hynix) - SEMI, VLSI, and Applied Materials

Ai is emerging and projected to drive the Market Size up to \$1 Trillion by 2030

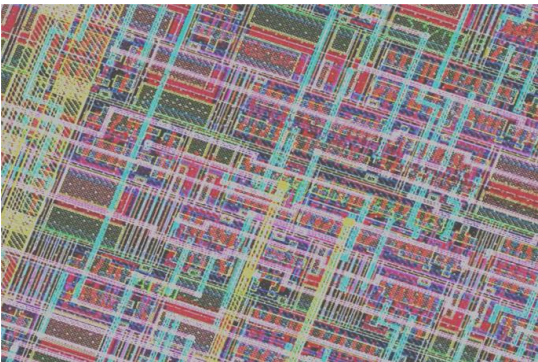
Customer Challenges – More TEM Analysis!



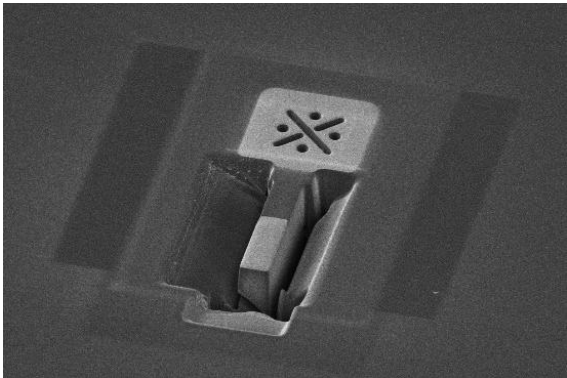
Device complexity is driving the need for TEM automation to meet growing sample demands

Key Steps in TEM Metrology

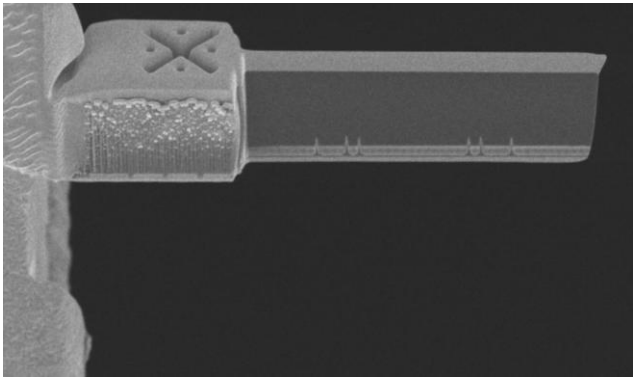
TEM Lamella Preparation and TEM Imaging



Wafer



Lamella
Milled on
wafer



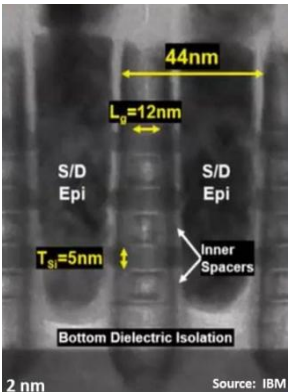
Lamella Welded to grid



Sample (Lamella) Preparation tools



TEM:
Fin-view



TEM: Gate
View



Imaging tools

Challenges in Sample prep for TEM Metrology

- Advanced logic: ~20-30 nm thick lamella
- 3D NAND / packaging: <70 nm, ; industry asking for >10um deep samples
- Robust, useful lamella
 - Centering and Thickness Accuracy metrics
- Operator Technical Expertise
- # of trained operators



Solutions

AUTOMATION!



Productivity



Yield



Operating Cost

Productivity

Faster cycle times and higher tool utilization

Yield

Automated workflows reduce process and Operator variability

Operating Cost

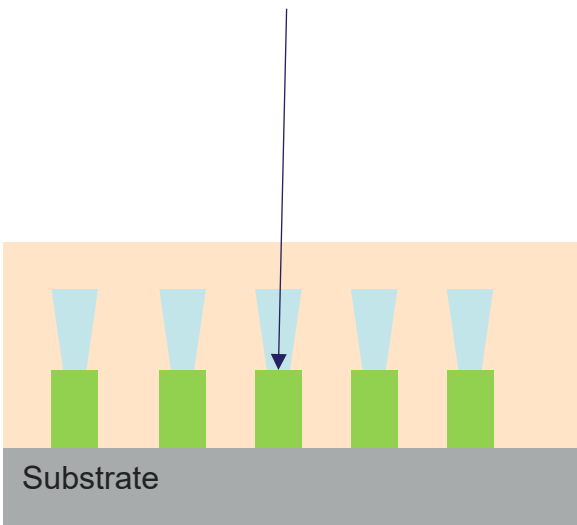
Lower OpEx through reduced labor and higher uptime

Automation is key to industrializing lamella production

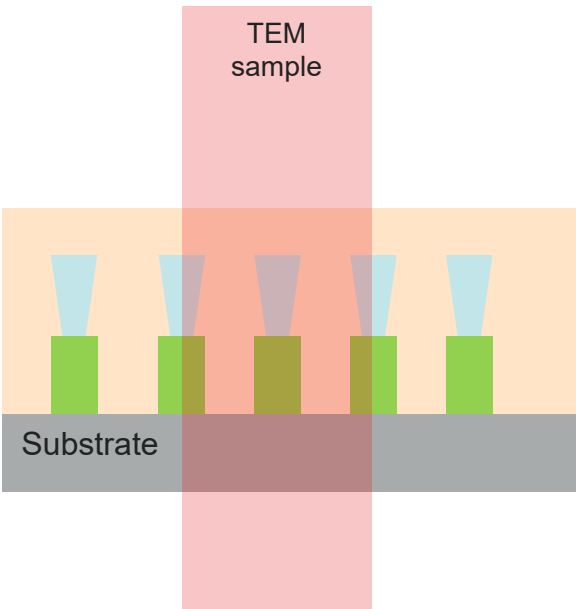
Critical Lamella Metrics

Lamella Centering Accuracy (LCA) & Lamella Thickness Accuracy (LTA)

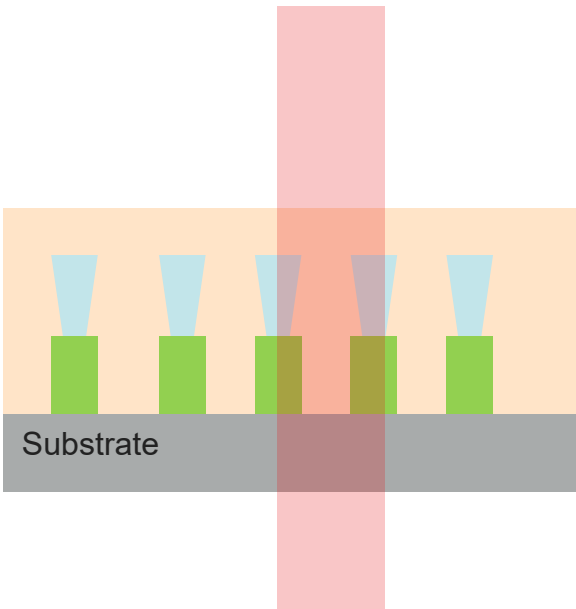
Feature of interest



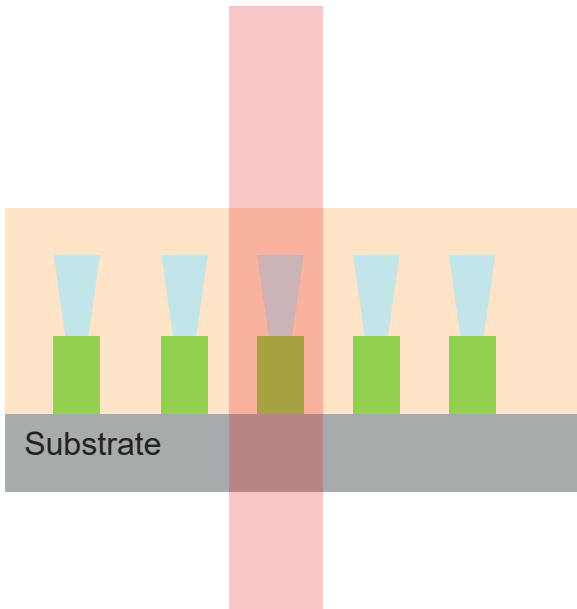
Thickness Error



Centering Error

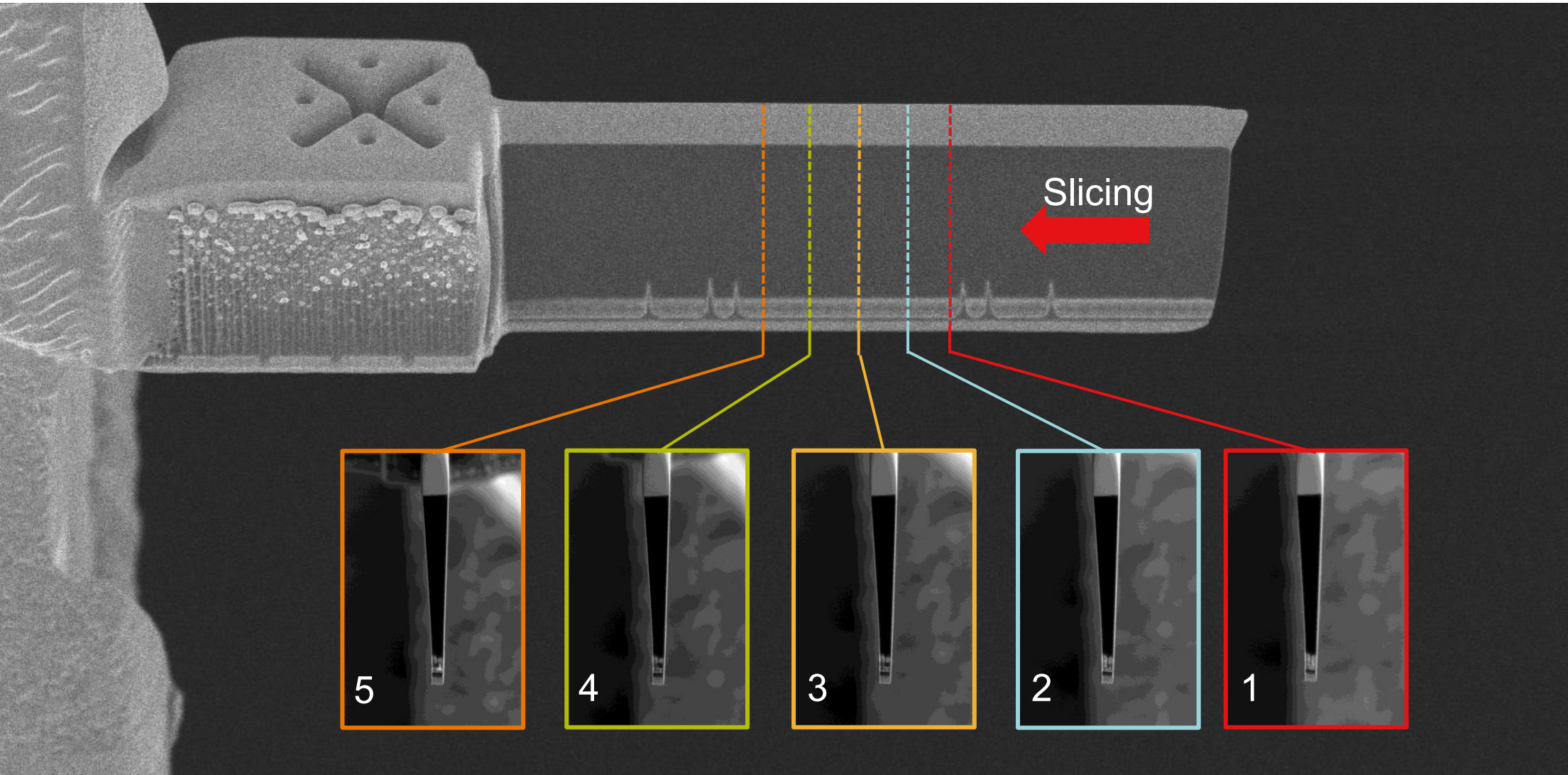


Acceptable



Cross-sectional representation of a device to be analyzed with TEM metrology

Sectioning for Lamella Quality Assessment

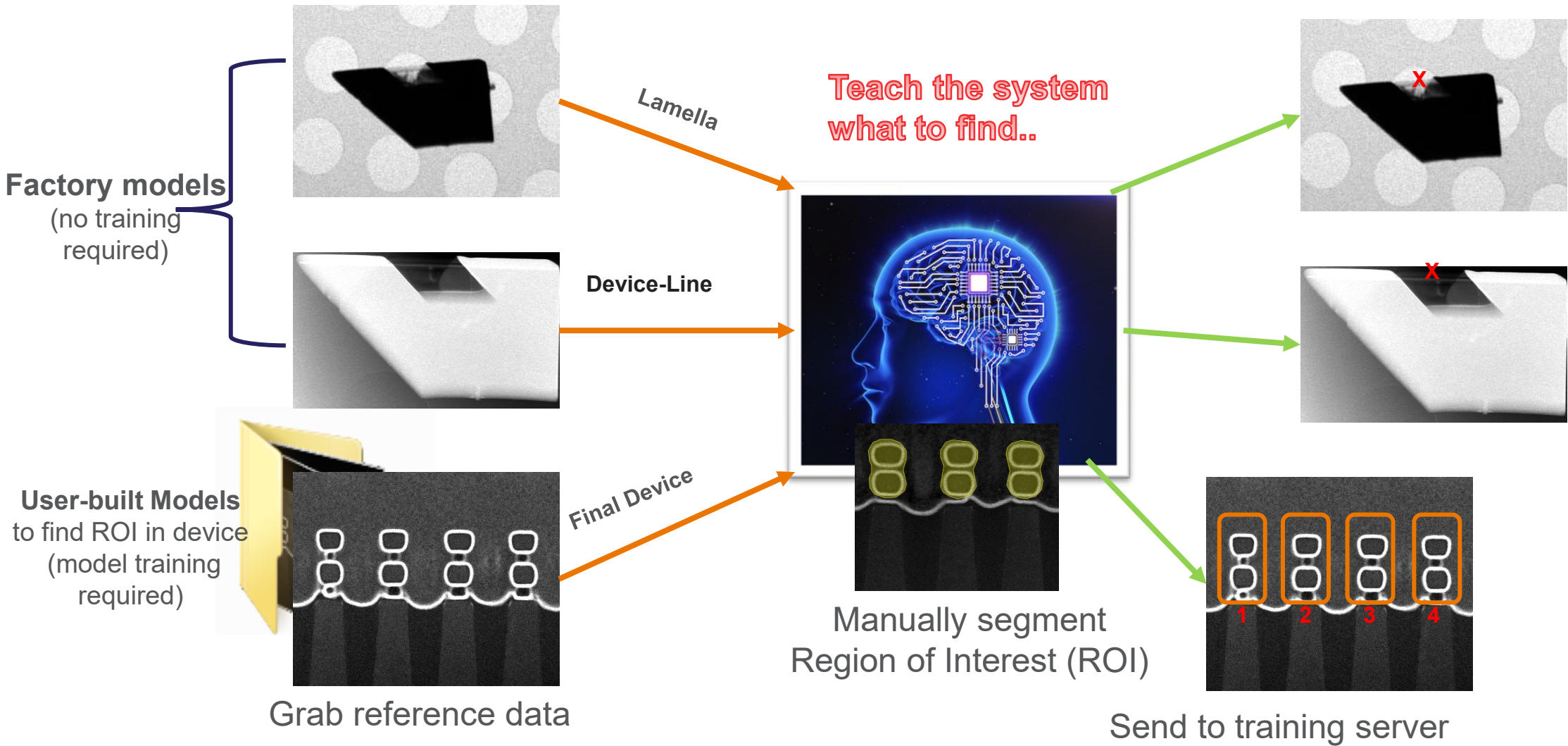


Automated End-point Detection Results



Automated Process Performance Metrics

Preparation Method/System	Typical LCA	Typical LTA
Manual Sample Preparation on Helios EXL	6nm, high operator dependance	6nm, high operator dependance
ExSolve G2 Automated TEM Sample Preparation	<4.4nm	<3.6nm
Vulcan Active Endpointing	<2nm	<2nm



Automated Material Handling for TEM Samples

1

Fresh LCs are pre-loaded into Helios

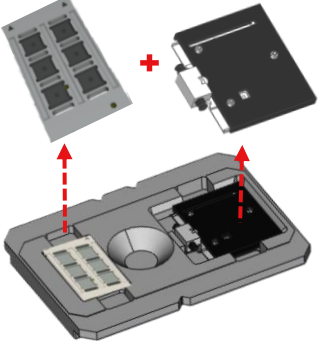


FLCC

LC

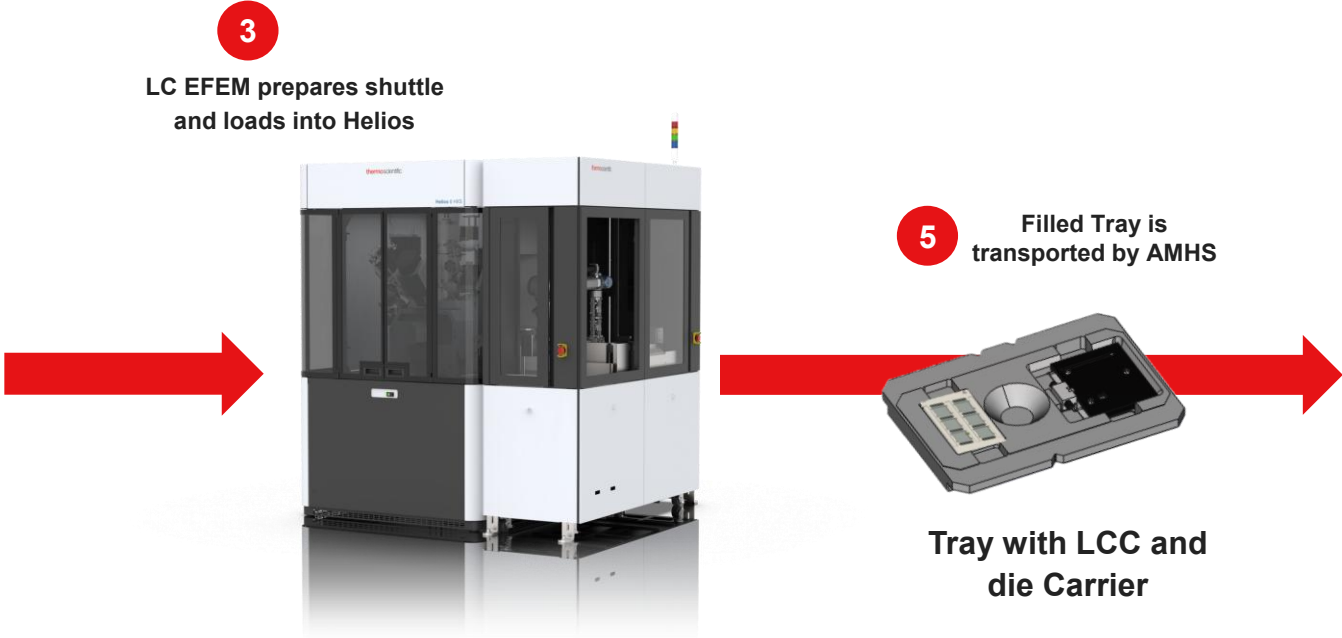
2

AMHS loads tray with die carrier and LCC



Die Carrier

LCC



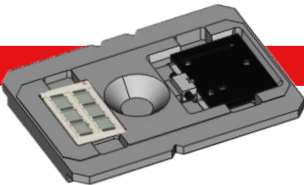
Helios 6HXS With LC EFEM

4

Lamellae are created in Helios automatically

5

Filled Tray is transported by AMHS



Tray with LCC and die Carrier



METRIOS 6S With LC EFEM

Summary

- **Market Pull**
AI + advanced architectures are driving massive TEM demand
- **Manual workflows cannot scale to fab-level throughput**
- **Automation is the Solution**
 - Automated lamella production
 - Automated imaging
 - Automated Material transfer & Data Connectivity – From Fab to Lab



Thank you